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12/18/01

U.S. UTILITY Patent Application

PATENT NUMBER and
ISSUE DATE

APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER
10024958	12/18/2001	430216	53	1756	Chen
**APPLICANTS: Buie Melisa; Stoebr Brigitte; Ruhl Guenther;					
**CONTINUING DATA VERIFIED: THIS APPLICATION IS A CIP OF PCT/US01/19282 06/15/2001					
** FOREIGN APPLICATIONS VERIFIED: GERMANY 101 46 935.7 09/24/2001					
PG-PUB		DO NOT PUBLISH <input type="checkbox"/>		RESCIND <input type="checkbox"/>	
Foreign priority claimed <input type="checkbox"/> yes <input type="checkbox"/> no 35 USC 119 conditions met <input type="checkbox"/> yes <input type="checkbox"/> no Verified and Acknowledged Examiners's initials				ATTORNEY DOCKET NO AMA/4213.P1/ETCH/METAL/JB	
TITLE : Etch process for photolithographic reticle manufacturing with improved etch bias U.S. DEPT. OF COMM./PAT. & TM-PTO-436L (Rev. 12-94)					

NOTICE OF ALLOWANCE MAILED		Assistant Examiner		CLAIMS ALLOWED	
				Total Claims	Print Claim for O.G.
ISSUE FEE		Primary Examiner		DRAWING	
Am unt Due	Date Paid			Sheets Drwg.	Figs. Drwg.
<input type="checkbox"/> TERMINAL DISCLAIMER		PREPARED FOR ISSUE		Applicati n Examiner	
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